

# Aka-Brief #6 Coated Sintered Carbides



Times are stated for a 300 mm preparation system and forces for an individual 40 mm dia. sample.

On a 250 mm system the times should be increased by 30%, on a 200 mm system by 100%.

With larger samples the force should be increased, with smaller samples decreased.

The rotational speed of the head (sample holder or sample mover plate) used is 150 rpm.

Time and force may vary depending on the equipment.

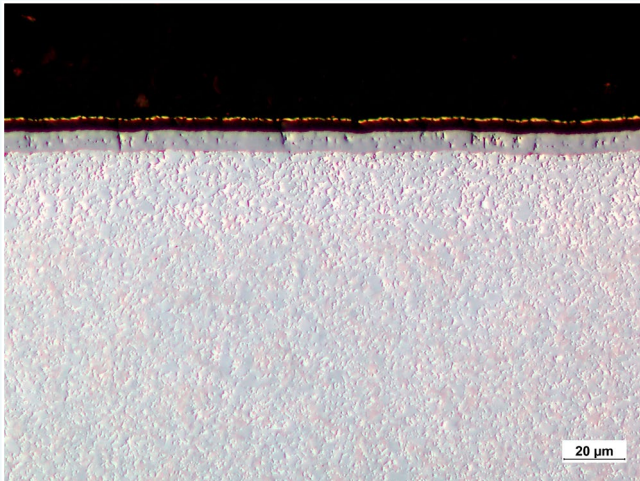
\* Step 4 is optional.

\*\* Prior to oxide polishing the polishing cloth should be wetted with water until the holder touches the polishing cloth. For the last 10 seconds of the oxide polishing step, the polishing cloth should be flushed with water to clean both sample(s) and polishing cloth.

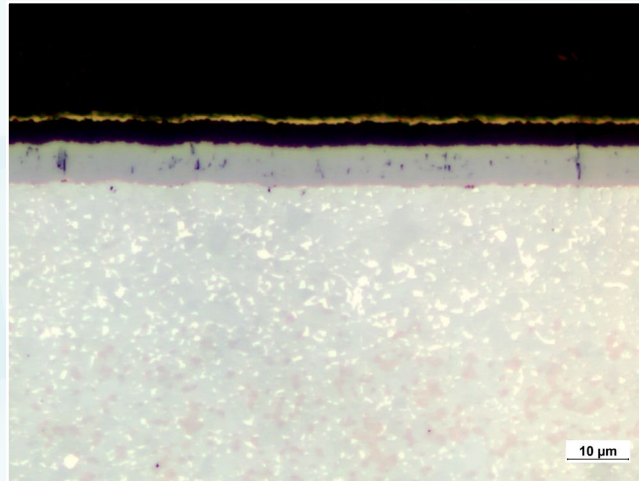


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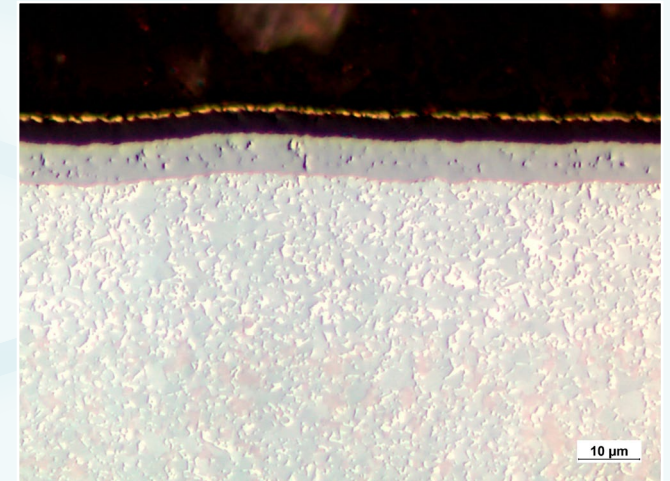
## FINAL RESULT



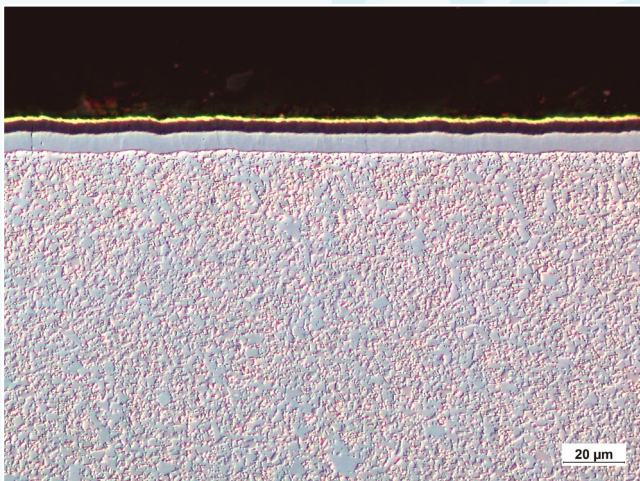
After 1 µm polishing, DIC, 500x



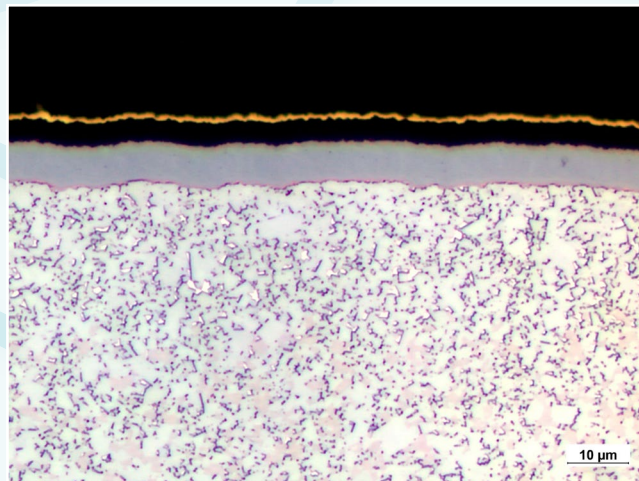
After 1 µm polishing, BF, 1000x



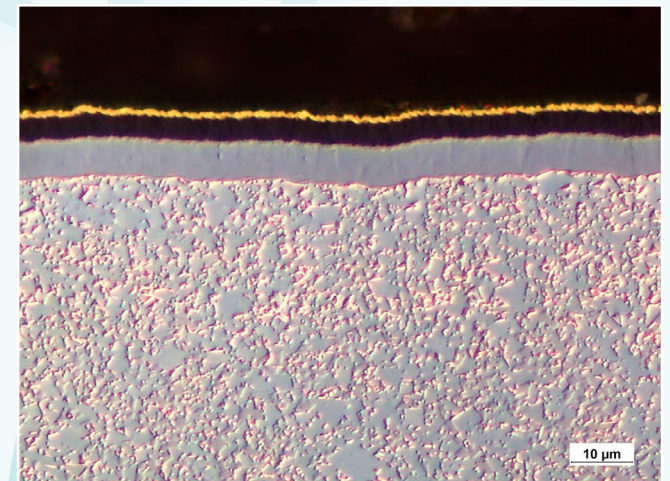
After 1 µm polishing, DIC, 1000x



After oxide polishing, DIC, 500x



After oxide polishing, BF, 1000x



After oxide polishing, DIC, 1000x